The documentation and process conversion measures necessary to comply with this revision shall be completed by 19 June 2012.

INCH-POUND

MIL-PRF-19500/614G 19 March 2012 SUPERSEDING MIL-PRF-19500/614F 19 November 2007

### PERFORMANCE SPECIFICATION SHEET

\* SEMICONDUCTOR DEVICE, FIELD EFFECT RADIATION HARDENED (TOTAL DOSE AND SINGLE EVENT EFFECTS) TRANSISTORS, N-CHANNEL, SILICON, TYPES 2N7380 AND 2N7381, JANTXV, M, D, R, F, G, AND H AND JANS, M, D, R, F, G, AND H

This specification is approved for use by all Departments and Agencies of the Department of Defense.

The requirements for acquiring the product described herein shall consist of this specification sheet and MIL-PRF-19500.

### 1. SCOPE

- 1.1 <u>Scope</u>. This specification covers the performance requirements for an N-channel, radiation hardened, (total dose and single event effects (SEE)) enhancement mode, MOSFET, power transistors intended for use in high density power switching applications. Two levels of product assurance are provided for each device type as specified in MIL-PRF-19500, with avalanche energy ratings (E<sub>AS</sub>) and maximum avalanche current (I<sub>AS</sub>). See 6.5 for JANHC and JANKC die versions.
  - 1.2 Physical dimensions. See figure 1 (TO-257AA).
  - 1.3 Maximum ratings. Unless otherwise specified,  $T_C = +25$ °C.

Туре	P <sub>T</sub> (1) T <sub>C</sub> = +25°C	$P_T$ $T_A = +25^{\circ}C$ (free air)	R <sub>θ</sub> JC (2)	$\begin{aligned} &\text{Min V}_{(BR)DSS} \\ &\text{V}_{GS} = 0 \text{ V} \\ &\text{I}_{D} = 1.0 \text{ mA dc} \end{aligned}$	I <sub>D1</sub> (3) (4) T <sub>C</sub> = +25°C	I <sub>D2</sub> (3) (4) T <sub>C</sub> = +100°C	$T_J$ and $T_{STG}$
	<u>W</u>	<u>W</u>	<u>°C/W</u>	V dc	A dc	A dc	<u>°C</u>
2N7380 2N7381	75 75	2 2	1.67 1.67	100 200	14.4 9.4	9.1 6.0	-55 to +150 -55 to +150

Туре	Is	I <sub>DM</sub> (5)	V <sub>GS</sub>	E <sub>AS</sub> max	I <sub>AS</sub>
	A dc	<u>A(pk)</u>	<u>V dc</u>	<u>mJ</u>	A dc
2N7380 2N7381	14.4 9.4	57.6 37.6	±20 ±20	150 150	14.4 9.4

(See notes next page)

AMSC N/A FSC 5961

<sup>\*</sup> Comments, suggestions, or questions on this document should be addressed to DLA Land and Maritime, ATTN: VAC, P.O. Box 3990, Columbus, OH 43218-3990, or emailed to Semiconductor@dscc.dla.mil. Since contact information can change, you may want to verify the currency of this address information using the ASSIST Online database at https://assist.daps.dla.mil/.

- 1.3 Maximum ratings. continued
- (1) Derate linearly by 0.6 W/ $^{\circ}$ C for T<sub>C</sub> > +25 $^{\circ}$ C.
- (2) See figure 2, thermal impedance curves.
- (3) The following formula derives the maximum theoretical I<sub>D</sub> limit. I<sub>D</sub> is limited by package and device construction.

$$I_{D} = \sqrt{\frac{T_{JM} - T_{C}}{\left(R_{\theta JC}\right) x \left(R_{DS}(\text{ on }) \text{ at } T_{JM}\right)}}$$

- (4) See figure 3, maximum drain current graph.
- (5)  $I_{DM} = 4 \times I_{D1}$  as calculated in note (3).
  - 1.4 <u>Primary electrical characteristics</u>. Unless otherwise specified,  $T_C = +25^{\circ}C$ .

Туре	$ \begin{array}{c} \text{Min } V_{(BR)DSS} \\ V_{GS} = 0 \end{array} $		S(th)1 ≥ V <sub>GS</sub>	$\begin{aligned} & I_{DSS} & max \\ & V_{GS} = 0 \\ & V_{DS} = 80 & percent \end{aligned}$		$I_{DS(on)1}$ (1) 2 V; $I_{D} = I_{D2}$		
	$I_D = 1.0 \text{ mA dc}$	$I_D = 1.0$	) mA dc	of rated V <sub>DS</sub>	$T_J = +25^{\circ}C$	$T_{J} = +150^{\circ}C$		
	<u>V dc</u>	<u>V dc</u>		μA dc	Ω	Ω		
		Min	Max					
2N7380	100	2.0 4.0		25	0.18	0.33		
2N7381	200	2.0	4.0	25	0.40	0.84		

- (1) Pulsed (see 4.5.1).
- 2. APPLICABLE DOCUMENTS
- 2.1 <u>General</u>. The documents listed in this section are specified in sections 3, 4, or 5 of this specification. This section does not include documents cited in other sections of this specification or recommended for additional information or as examples. While every effort has been made to ensure the completeness of this list, document users are cautioned that they must meet all specified requirements of documents cited in sections 3, 4, or 5 of this specification, whether or not they are listed.
  - 2.2 Government documents.
- 2.2.1 <u>Specifications, standards, and handbooks</u>. The following specifications, standards, and handbooks form a part of this document to the extent specified herein. Unless otherwise specified, the issues of these documents are those cited in the solicitation or contract.

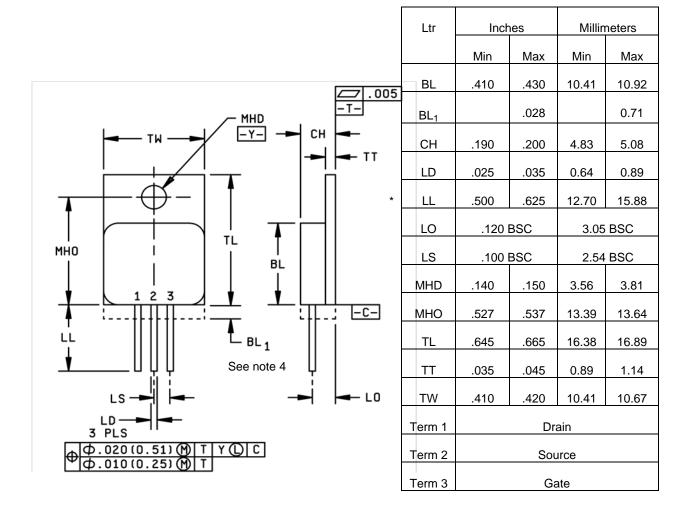
### DEPARTMENT OF DEFENSE SPECIFICATIONS

MIL-PRF-19500 - Semiconductor Devices, General Specification for.

### DEPARTMENT OF DEFENSE STANDARDS

MIL-STD-750 - Test Methods for Semiconductor Devices.

- \* (Copies of these documents are available online at <a href="https://assist.daps.dla.mil/quicksearch/">https://assist.daps.dla.mil/quicksearch/</a> or <a href="https://assist.daps.dla.mil/">https://assist.daps.dla.mil/</a> or from the Standardization Document Order Desk, 700 Robbins Avenue, Building 4D, Philadelphia, PA 19111-5094.)
- \* 2.3 <u>Order of precedence</u>. Unless otherwise noted herein or in the contract, in the event of a conflict between the text of this document and the references cited herein, the text of this document takes precedence. Nothing in this document, however, supersedes applicable laws and regulations unless a specific exemption has been obtained.



### NOTES:

- 1. Dimensions are in inches.
- 2. Millimeters are given for general information only.
- 3. All terminals are isolated from case.
- 4. This area is for the lead feed-through eyelets (configuration is optional, but will not extend beyond this zone).
- 5. In accordance with ASME Y14.5M, diameters are equivalent to φx symbology.
  - \* FIGURE 1. Dimensions and configuration (TO-257AA).

- 3. REQUIREMENTS
- 3.1 General. The individual item requirements shall be as specified in MIL-PRF-19500 and as modified herein.
- 3.2 <u>Qualification</u>. Devices furnished under this specification shall be products that are manufactured by a manufacturer authorized by the qualifying activity for listing on the applicable qualified manufacturer's list (QML) before contract award (see 4.2 and 6.3).
- 3.3 <u>Abbreviations, symbols, and definitions</u>. Abbreviations, symbols, and definitions used herein shall be as specified in MIL-PRF-19500 and as follows.

I<sub>AS</sub> ....... Rated avalanche current, nonrepetitive. nC ......nano Coulomb.

- 3.4 Interface and physical dimensions. Interface and physical dimensions shall be as specified in MIL-PRF-19500, and on figure 1 (TO-257AA). Methods used for electrical isolation of the terminal feedthroughs shall employ materials that contain a minimum of 90 percent  $AL_2O_3$  (ceramic). Examples of such construction techniques are metallized ceramic eyelets or ceramic walled packages.
- 3.4.1 <u>Lead finish</u>. Lead finish shall be solderable in accordance with MIL-PRF-19500, MIL-STD-750, and herein. Where a choice of lead finish is desired, it shall be specified in the acquisition document (see 6.2).
  - 3.4.2 <u>Internal construction</u>. Multiple chip construction shall not be permitted.
  - 3.5 Marking. Marking shall be in accordance with MIL-PRF-19500.
  - 3.6 <u>Electrostatic discharge protection</u>. The devices covered by this specification require electrostatic protection.
- 3.6.1 <u>Handling</u>. MOS devices must be handled with certain precautions to avoid damage due to the accumulation of static charge. The following handling procedures shall be followed:
  - a. Devices shall be handled on benches with conductive handling devices.
  - b. Ground test equipment, tools, and personnel handling devices.
  - c. Do not handle devices by the leads.
  - d. Store devices in conductive foam or carriers.
  - e. Avoid use of plastic, rubber, or silk in MOS areas.
  - f. Maintain relative humidity above 50 percent, if practical.
  - g. Care shall be exercised, during test and troubleshooting, to apply not more than maximum rated voltage to any lead.
  - h. Gate must be terminated to source. R  $\leq$  100 k $\Omega$ , whenever bias voltage is to be applied drain to source.
- 3.7 <u>Electrical performance characteristics</u>. Unless otherwise specified herein, the electrical performance characteristics are as specified in 1.3, 1.4, and table I herein.
  - 3.8 Electrical test requirements. The electrical test requirements shall be table I as specified herein.
- 3.9 <u>Workmanship</u>. Semiconductor devices shall be processed in such a manner as to be uniform in quality and shall be free from other defects that will affect life, serviceability, or appearance.

### 4. VERIFICATION

- 4.1 Classification of inspections. The inspection requirements specified herein are classified as follows:
  - a. Qualification inspection (see 4.2).
  - b. Screening (see 4.3).
  - c. Conformance inspection (see 4.4 and tables I and II).
- 4.2 Qualification inspection. Qualification inspection shall be in accordance with MIL-PRF-19500 and as specified herein.
- 4.2.1 <u>Group E qualification</u>. Group E inspection shall be performed for qualification or re-qualification only. In case qualification was awarded to a prior revision of the specification sheet that did not request the performance of table III tests, the tests specified in table III herein that were not performed in the prior revision shall be performed on the first inspection lot of this revision to maintain qualification.

\* 4.3 <u>Screening (JANS and JANTXV levels only)</u>. Screening shall be in accordance with table E-IV of MIL-PRF-19500, and as specified herein. The following measurements shall be made in accordance with table I herein. Devices that exceed the limits of table I herein shall not be acceptable.

Screen (see table E-IV	Measi	urement			
of MIL-PRF-19500) (1) (2)	JANS level	JANTXV level			
(3)	Gate stress test (see 4.3.1)	Gate stress test (see 4.3.1)			
(3)	Method 3470 of MIL-STD-750. (see 4.3.2)	Method 3470 of MIL-STD-750. (see 4.3.2)			
(3) 3c	Method 3161 of MIL-STD-750 (see 4.3.3)	Method 3161 of MIL-STD-750 (see 4.3.3)			
9	I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , I <sub>DSS1</sub> , subgroup 2 of table I herein	Not applicable			
10	Method 1042 of MIL-STD-750, test condition B	Method 1042 of MIL-STD-750, test condition B			
11	$\begin{split} &I_{\text{GSSF1}},I_{\text{GSSR1}},I_{\text{DSS1}},r_{\text{DS(on)1}},V_{\text{GS(th)1}}\\ &\text{Subgroup 2 of table I herein.}\\ &\Delta I_{\text{GSSF1}}=\pm20\text{ nA dc or}\pm100\text{ percent of initial value, whichever is greater.}\\ &\Delta I_{\text{GSSR1}}=\pm20\text{ nA dc or}\pm100\text{ percent of initial value, whichever is greater.}\\ &\Delta I_{\text{DSS1}}=\pm25\mu\text{A dc or}\pm100\text{ percent of initial value, whichever is greater.} \end{split}$	I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , I <sub>DSS1</sub> , r <sub>DS(on)1</sub> , V <sub>GS(th)1</sub> Subgroup 2 of table I herein.			
12	Method 1042 of MIL-STD-750, test condition A	Method 1042 of MIL-STD-750, test condition A			
13	Subgroup 2 and 3 of table I herein. $\Delta I_{GSSF1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 25$ $\mu$ A dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 25$ $\mu$ A dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DS(on)1} = \pm 20$ percent of initial value. $\Delta V_{GS(th)1} = \pm 20$ percent of initial value.	Subgroup 2 of table I herein. $\Delta I_{GSSF1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{GSSR1} = \pm 20 \text{ nA dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{DSS1} = \pm 25  \mu \text{A dc or } \pm 100 \text{ percent of initial value, whichever is greater.}$ $\Delta I_{DS(n)1} = \pm 20 \text{ percent of initial value.}$ $\Delta I_{DS(n)1} = \pm 20 \text{ percent of initial value.}$ $\Delta I_{DS(n)1} = \pm 20 \text{ percent of initial value.}$			

- (1) At the end of the test program,  $I_{\text{GSSF1}},\,I_{\text{GSSR1}},$  and  $I_{\text{DSS1}}$  are measured.
- (2) An out-of-family program to characterize I<sub>GSSF1</sub>, I<sub>GSSR1</sub>, I<sub>DSS1</sub>, and V<sub>GS(th)1</sub> shall be invoked.
- (3) Shall be performed anytime after temperature cycling, screen 3a; JANTXV level does not need to be repeated in screening requirements.

- 4.3.1 Gate stress test. Apply  $V_{GS} = \pm 30 \text{ V}$  minimum for  $t = 250 \,\mu\text{s}$  minimum.
- 4.3.2 Single pulse avalanche energy (EAS).
  - a. Peak current (I<sub>AS</sub>)......I<sub>D1</sub>.
  - b. Peak gate voltage (V<sub>GS</sub>)...... 12 V.

  - d. Initial case temperature ......+25°C +10°C, -5°C.
  - e. Inductance ......  $\left[ \frac{2E_{{\scriptscriptstyle AS}}}{\left(I_{{\scriptscriptstyle DI}}\right)^2} \right] \!\! \left[ \! \frac{V_{{\scriptscriptstyle BR}} V_{{\scriptscriptstyle DD}}}{V_{{\scriptscriptstyle BR}}} \right] \!\! \text{mH minimum.}$
  - f. Number of pulses to be applied ...... 1 pulse minimum.
- 4.3.3 <u>Thermal impedance</u>. The thermal impedance measurements shall be performed in accordance with method 3161 of <u>MIL-STD-750</u> using the guidelines in that method for determining  $I_M$ ,  $I_H$ ,  $t_H$ ,  $t_{SW}$ , (and  $V_H$  where appropriate). Measurement delay time ( $t_{MD}$ ) = 70  $\mu$ s max. See table III, group E, subgroup 4 herein.
- 4.4 <u>Conformance inspection</u>. Conformance inspection shall be in accordance with MIL-PRF-19500 and as specified herein.
- 4.4.1 <u>Group A inspection</u>. Group A inspection shall be conducted in accordance with MIL-PRF-19500 and table I herein. Electrical measurements (end-points) shall be in accordance with table I, subgroup 2 herein.
- 4.4.2 <u>Group B inspection</u>. Group B inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VIA (JANS) and table E-VIB (JANTXV) of MIL-PRF-19500, and as follows. Electrical measurements (end-points) shall be in accordance with table I, subgroup 2 herein.
  - 4.4.2.1 Group B inspection, table E-VIA (JANS) of MIL-PRF-19500.

Subgroup	Method	<u>Condition</u>
В3	1051	Condition G.
B4	1042	The heating cycle shall be 1 minute minimum, 2,000 cycles. No heat sink nor forced air cooling on the device shall be permitted.
B5	1042	Condition A; $V_{DS}$ = 100 percent of rated; $T_A$ = +175°C, $t$ = 120 hours or $T_A$ = +150°C, $t$ = 240 hours; read and record $V_{BR(DSS)}$ (pre and post) at $I_D$ = 1 mA; read and record $I_{DSS}$ (pre and post), in accordance with table I, subgroup 2.
B5	1042	Condition B; $V_{GS}$ = 100 percent of rated $T_A$ = +175°C, t = 24 or $T_A$ = +150°C, t = 48 hours.

### 4.4.2.2 Group B inspection, table E-VIB (JANTXV) of MIL-PRF-19500.

<u>Subgroup</u>	Method	Condition
B2	1051	Condition G.
В3	1042	The heating cycle shall be 1 minute minimum.

4.4.3 <u>Group C inspection</u>. Group C inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VII of MIL-PRF-19500, and as follows. Electrical measurements (end-points) shall be in accordance with table I, subgroup 2 herein.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
C2	2036	Test condition A, weight = 10 lbs, t = 10 seconds.
C5	3161	See 4.3.3, $R_{\theta JC(max)} = 1.67^{\circ}C/W$
C6	1042	The heating cycle shall be 1 minute minimum, 6,000 cycles. No heat sink nor forced air cooling on the device shall be permitted.

- 4.4.4 <u>Group D Inspection</u>. Group D inspection shall be conducted in accordance with appendix E, table E-VIII of MIL-PRF-19500 and table II herein.
- 4.4.5 <u>Group E inspection</u>. Group E inspection shall be conducted in accordance with the conditions specified for subgroup testing in appendix E, table E-IX of MIL-PRF-19500 and as specified herein. Electrical measurements (end-points) shall be in accordance with table I, subgroup 2 herein.
  - 4.5 Methods of inspection. Methods of inspection shall be as specified in appropriate tables and as follows.
- 4.5.1 <u>Pulse measurements</u>. Conditions for pulse measurements shall be as specified in section 4 of MIL-STD-750.

# \* TABLE I. Group A inspection.

Inspection 1/		MIL-STD-750	Symbol	Lir	mits	Unit
	Method	Condition		Min	Max	
Subgroup 1						
Visual and mechanical inspection	2071					
Subgroup 2						
Thermal impedance 2/	3161	See 4.3.3	Z <sub>θJC</sub>			°C/W
Breakdown voltage drain to source	3407	$V_{GS} = 0$ , $I_D = 1$ mA dc, bias condition C	V <sub>(BR)DSS</sub>			
2N7380 2N7381				100 200		V dc V dc
Gate to source voltage (threshold)	3403	$V_{DS} \ge V_{GS}$ , $I_D = 1.0 \text{ mA}$	V <sub>GS(th)1</sub>	2.0	4.0	V dc
Gate current	3411	$V_{GS} = +20 \text{ V dc}, V_{DS} = 0,$ bias condition C	I <sub>GSSF1</sub>		+100	nA dc
Gate current	3411	$V_{GS} = -20 \text{ V dc}, V_{DS} = 0,$ bias condition C	I <sub>GSSR1</sub>		-100	nA dc
Drain current	3413	$V_{GS} = 0$ , $V_{DS} = 80$ percent of rated $V_{DS}$ , bias condition C	I <sub>DSS1</sub>		25	μA dc
Static drain to source on-state resistance	3421	$V_{GS}$ = 12 V dc, condition A, pulsed (see 4.5.1), $I_D$ = rated $I_{D2}$ (see 1.3)	r <sub>DS(on)1</sub>			
2N7380 2N7381					0.18 0.40	$\Omega$
Static drain to source on-state resistance	3421	$V_{GS} = 12 \text{ V dc}$ , condition A, pulsed (see 4.5.1), $I_D = \text{rated } I_{D1}$ (see 1.3)	r <sub>DS(on)2</sub>		_	
2N7380 2N7381					0.20 0.49	$\Omega$ $\Omega$
Forward voltage (source drain diode)	4011	$V_{GS} = 0$ , $I_D = \text{rated } I_{D1}$ pulsed (see 4.5.1)	$V_{SD}$			
2N7380 2N7381		,			1.8 1.4	V dc V dc

\* TABLE I. Group A inspection - Continued.

Inspection <u>1</u> /		MIL-STD-750	Symbol	Liı	Unit	
	Method	Condition		Min	Max	
Subgroup 3						
High temperature operation:		T <sub>A</sub> = +125°C				
Gate current	3411	Bias condition C, $V_{GS} = \pm 20 \text{ V dc}$ , $V_{DS} = 0$	$I_{GSS2}$		±200	nA dc
Drain current	3413	Bias condition C, $V_{GS} = 0$ , $V_{DS} = 80$ percent of rated $V_{DS}$	I <sub>DSS3</sub>		0.25	mA dc
Static drain to source on-state	3421	$V_{GS}$ = 12 V dc, pulsed (see 4.5.1), $I_D$ = rated $I_{D2}$	r <sub>DS(on)3</sub>			
2N7380 2N7381					0.35 0.75	Ω Ω
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}, \ I_D = 1.0 \ mA \ dc$	$V_{\text{GS(th)2}}$	1.0		V dc
Low temperature operation:		T <sub>A</sub> = -55°C				
Gate to source voltage (threshold)	3403	$V_{DS} \ge V_{GS}$ , $I_D$ = 1.0 mA dc	$V_{\text{GS(th)3}}$		5.0	V dc
Subgroup 4						
Switching time test	3472	$\begin{split} I_D &= \text{rated } I_{D1},  V_{GS} = 12  \text{V dc, gate} \\ \text{drive impedance} &= 7.5  \Omega,  V_{DD} = 50 \\ \text{percent of } V_{BR(DSS)} \end{split}$				
Turn-on delay time			$t_{d(on)}$		25	ns
Rise time 2N7380 2N7381			t <sub>r</sub>		60 50	ns ns
Turn-off delay time 2N7380 2N7381			$t_{\text{d(off)}}$		40 70	ns ns
Fall time 2N7380 2N7381			t <sub>f</sub>		30 60	ns ns

## \* TABLE I. Group A inspection - Continued.

Inspection <u>1</u> /		MIL-STD-750	Symbol	Lir	Unit	
	Method	Condition		Min	Max	
Subgroup 4 - Continued.						
Forward transconductance	3475	$I_D = I_{D2}$ , $V_{DD} = 15 \text{ V dc see } 4.5.1$	g <sub>fs</sub>	2.5		s
Subgroup 5						
* Safe operating area test (high voltage)	3474	See figure 4, $t_p$ = 10 ms, $V_{DS}$ = 80 percent of rated $V_{BR(DSS)}$ , $V_{DS} \le$ 200 V maximum				
Electrical measurements		See table I, subgroup 2				
Subgroup 6						
Not applicable						
Subgroup 7						
Gate charge	3471	Condition B				
On-state gate charge 2N7380 2N7381			Q <sub>g(on)</sub>		40 50	nC nC
Gate to source charge			$Q_gs$		10	nC
Gate to drain charge 2N7380 2N7381			$Q_gd$		20 25	nC nC
Reverse recovery time	3473	$d_i/d_t \le 100 \text{ A/}\mu\text{s}, V_{DD} \le 50 \text{ V},$	t <sub>rr</sub>			
2N7380 2N7381		$I_D = I_{D1}$			275 460	ns ns

 <sup>1/</sup> For sampling plan, see MIL-PRF-19500.
 2/ This test required for the following end-point measurements only: Group B, subgroups 3 and 4 (JANS). Group B, subgroups 2 and 3 (JANTXV).

Group C, subgroups 2 and 6.

Group E, subgroup 1.

TABLE II. Group D inspection.

Inspection	MI	IL-STD-750	Symbol		Pre-irradiation limits			Post-irradiation limits				Unit
<u>1</u> / <u>2</u> / <u>3</u> /	Method	Conditions										
				M, D,	and R	F, G, a	and H <u>4</u> /	M, D,	and R	F, G, ar	nd H <u>4</u> /	
				Min	Max	Min	Max	Min	Max	Min	Max	
Subgroup 2		T <sub>C</sub> = +25°C										
Steady-state total dose irradiation (V <sub>GS</sub> bias)	1019	$V_{GS} = 12 \text{ V},$ $V_{DS} = 0$										
Steady-state total dose irradiation (V <sub>DS</sub> bias)		$V_{GS} = 0$ , $V_{DS} =$ 80 percent of rated $V_{DS}$ (pre- irradiation)										
End-point electrical:												
Breakdown voltage, drain to source	3407	V <sub>GS</sub> = 0, I <sub>D</sub> = 1 mA, bias condition C	V <sub>(BR)DSS</sub>									
2N7380 2N7381				100 200		100 200		100 200		100 200		V dc V dc
Gate to source voltage (threshold)	3403	$V_{DS} \ge V_{GS}$ , $I_D = 1 \text{ mA}$	V <sub>GS(th)</sub>	2.0	4.0	2.0	4.0	2.0	4.0	1.25	4.5	V dc
Gate current	3411	$V_{GS} = 20 \text{ V},$ $V_{DS} = 0 \text{ V}, \text{ bias}$ condition C	I <sub>GSSF1</sub>		100		100		100		100	nA dc
Gate current	3411	$V_{GS} = 20 \text{ V},$ $V_{DS} = 0, \text{ bias}$ condition C	I <sub>GSSR1</sub>		-100		-100		-100		-100	nA dc

TABLE II. Group D inspection - Continued.

Inspection	MIL-STD-750		Symbol			adiatior nits	า			adiation		Unit
<u>1</u> / <u>2</u> / <u>3</u> /	Method	Conditions										
				M, D,	and R	F, G, a	and H <u>4</u> /	M, D,	and R	F, G, ar	nd H <u>4</u> /	
				Min	Max	Min	Max	Min	Max	Min	Max	
Subgroup 2 - Continued		T <sub>C</sub> = +25°C										
Drain current	3413	$V_{GS} = 0$ , bias condition C, $V_{DS} = 80$ percent of rated $V_{DS}$ (pre- irradiation)	I <sub>DSS</sub>									
2N7380 2N7381		,			25 25		25 25		25 25		50 50	μΑ dc μΑ dc
Static drain to source on-state voltage 2N7380 2N7381	3405	$V_{GS}$ = 12 V, condition A pulsed, see 4.5.1. $I_D$ = $I_{D2}$	V <sub>DS(ON)</sub>		1.638 2.4		1.638 2.4		1.638 2.4		2.184 3.18	V dc V dc
Forward voltage source drain diode	4011	$V_{GS} = 0$ , $I_D = I_{D1}$ , bias condition C	V <sub>SD</sub>									
2N7380 2N7381					1.8 1.4		1.8 1.4		1.8 1.4		1.8 1.4	V V

For sampling plan, see MIL-PRF-19500. Separate samples shall be pulled for each bias.

Group D qualification may be performed anytime prior to lot formation. Wafers qualified to these group D QCI requirements may be used for any other specification sheet utilizing the same die design.

The "H" designation represents devices which pass end-points at M, D, R, F, G, and H designated total-Ionizing-dose (TID).

# \* TABLE III. Group E inspection (all quality levels) - for qualification or re-qualification only.

Inspection		Sample	
inspection			plan
	Method	Conditions	
Subgroup 1			45 devices, c = 0
Temperature cycling	1051	Test condition G, 500 cycles	
Hermetic seal Fine leak Gross leak	1071		
Electrical measurements		See table I, subgroup 2	
Subgroup 2 1/			45 devices, c = 0
Steady-state reverse bias	1042	Condition A, 1,000 hours	0 = 0
Electrical measurements		See table I, subgroup 2	
Steady-state gate bias	1042	Condition B, 1,000 hours	
Electrical measurements		See table I, subgroup 2	
Subgroup 4			Sample size N/A
Thermal impedance curves		See MIL-PRF-19500.	N/A
Subgroup 10			22 devices, c = 0
Commutating diode for safe operating area test procedure for measuring dv/dt during reverse recovery of power MOSFET transistors or insulated gate bipolar transistors	3476	Test conditions shall be derived by the manufacturer	

\* TABLE III. Group E inspection (all quality levels) - for qualification or re-qualification only - Continued.

		Qualification and large lot	
Inspection	Method	MIL-STD-750  Conditions	quality conformance inspection
Subgroup 11			3 devices
SEE <u>2</u> / <u>3</u> / <u>4</u> /	1080	See figure 5.	
Electrical measurements <u>5</u> /		I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , and I <sub>DSS1</sub> in accordance with table I, subgroup 2	
SEE irradiation		Fluence = 3E5 ±20 percent ions/cm <sup>2</sup> Flux = 2E3 to 2E4 ions/cm <sup>2</sup> /sec, temperature = +25 ±5 °C	
2N7380		Surface LET = $28 \text{ MeV-cm}^2/\text{mg} \pm 5\%$ range = $42.8  \mu\text{m} \pm 7.5\%$ , energy = $283.3 \text{ MeV} \pm 7.5\%$ In-situ bias conditions: $V_{DS} = 100 \text{ V}$ and $V_{GS} = -10 \text{ V}$ $V_{DS} = 80 \text{ V}$ and $V_{GS} = -15 \text{ V}$ $V_{DS} = 60 \text{ V}$ and $V_{GS} = -20 \text{ V}$ (typical $4.53 \text{ MeV/nucleon}$ at Brookhaven National Lab Accelerator)	
2N7381		In-situ bias conditions: $V_{DS}$ = 190 V and $V_{GS}$ = 0 V $V_{DS}$ = 180 V and $V_{GS}$ = -5 V $V_{DS}$ = 170 V and $V_{GS}$ = -10 V $V_{DS}$ = 125 V and $V_{GS}$ = -15 V (nominal 4.53 MeV/nucleon at Brookhaven National Lab Accelerator)	
2N7380		Surface LET = 37 MeV-cm $^2$ /mg ±5%, range = 39 µm ±5%, energy = 305 MeV ±5% In-situ bias conditions: $V_{DS}$ = 100 V and $V_{GS}$ = 0 V $V_{DS}$ = 90 V and $V_{GS}$ = -5 V $V_{DS}$ = 70 V and $V_{GS}$ = -10 V $V_{DS}$ = 50 V and $V_{GS}$ = -15 V (typical 3.77 MeV/nucleon at Brookhaven National Lab Accelerator)	
2N7381		In-situ bias conditions: $V_{DS}$ = 100 V and $V_{GS}$ = -10 V $V_{DS}$ = 50 V and $V_{GS}$ = -15 V (typical 3.77 MeV/nucleon at Brookhaven National Lab Accelerator)	
Electrical measurements <u>5</u> /		I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , and I <sub>DSS1</sub> in accordance with table I, subgroup 2	

A separate sample for each test shall be pulled.

<sup>&</sup>lt;u>1/</u> <u>2</u>/ Group E qualification of SEE testing may be performed prior to lot formation. Qualification may be extended to other specification sheets utilizing the same structurally identical die design.

Device qualification to a higher level LET is sufficient to qualify all lower level LETs.

The sampling plan applies to each bias condition.

Examine I<sub>GSSF1</sub>, I<sub>GSSR1</sub> and I<sub>DSS1</sub> before and following SEE irradiation to determine acceptability for each bias condition. Other test conditions in accordance with table I, subgroup 2, may be performed at the manufacturer's option.

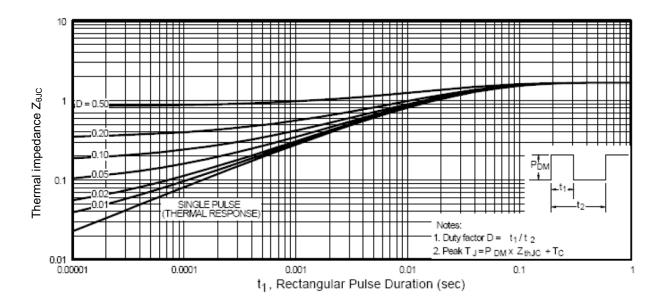
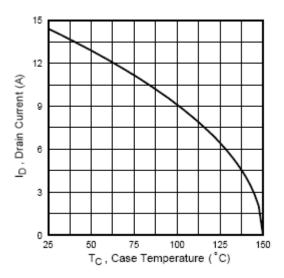


FIGURE 2. Thermal impedance curves.

## 2N7380



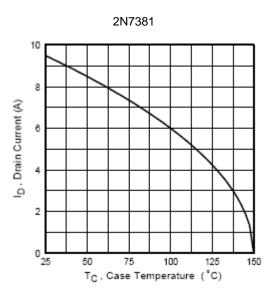


FIGURE 3. Maximum drain current versus case temperature graphs.

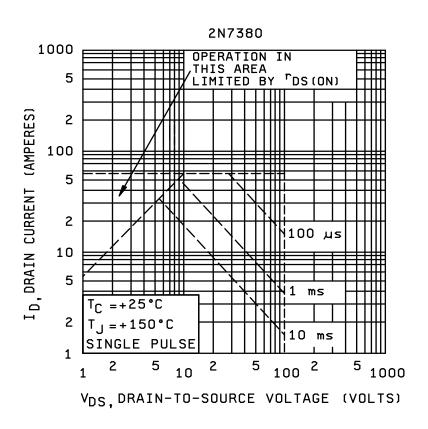


FIGURE 4. Safe operating area graphs.

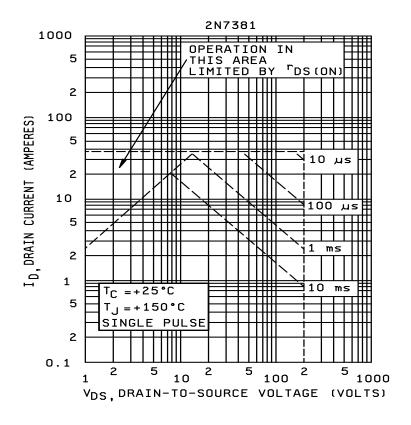
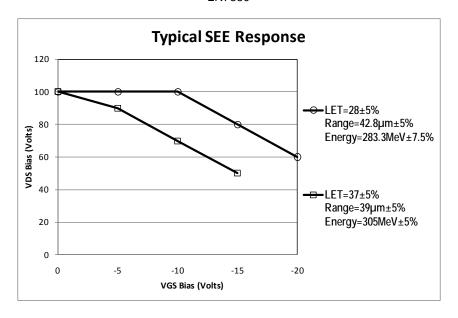
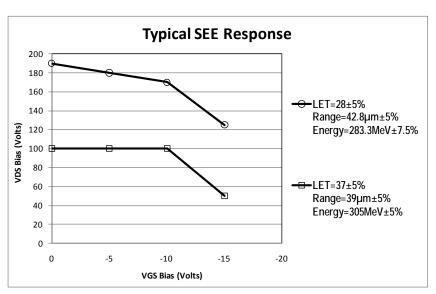


FIGURE 4. <u>Safe operating area graphs</u> - Continued.

### 2N7380



### 2N7381



\* FIGURE 5. Typical single event effects safe operating area graphs.

### 5. PACKAGING

5.1 <u>Packaging</u>. For acquisition purposes, the packaging requirements shall be as specified in the contract or order (see 6.2). When packaging of materiel is to be performed by DoD or in-house contractor personnel, these personnel need to contact the responsible packaging activity to ascertain packaging requirements. Packaging requirements are maintained by the Inventory Control Point's packaging activities within the Military Service or Defense Agency, or within the Military Service's system commands. Packaging data retrieval is available from the managing Military Department's or Defense Agency's automated packaging files, CD-ROM products, or by contacting the responsible packaging activity.

### 6. NOTES

(This section contains information of a general or explanatory nature that may be helpful, but is not mandatory. The notes specified in MIL-PRF-19500 are applicable to this specification.)

- 6.1 <u>Intended use</u>. Semiconductors conforming to this specification are intended for original equipment design applications and logistic support of existing equipment.
  - 6.2 Acquisition requirements. Acquisition documents should specify the following:
    - a. Title, number, and date of this specification.
    - b. Packaging requirements (see 5.1).
    - c. Lead finish (see 3.4.1).
    - d. Product assurance level and type designator.
- e. For acquisition of RHA designated devices, table II, subgroup 1 testing of group D herein is optional.
   If subgroup 1 is desired, it must be specified in the contract.
- \* 6.3 Qualification. With respect to products requiring qualification, awards will be made only for products which are, at the time of award of contract, qualified for inclusion in Qualified Manufacturers List (QML 19500) whether or not such products have actually been so listed by that date. The attention of the contractors is called to these requirements, and manufacturers are urged to arrange to have the products that they propose to offer to the Federal Government tested for qualification in order that they may be eligible to be awarded contracts or orders for the products covered by this specification. Information pertaining to qualification of products may be obtained from DLA Land and Maritime, ATTN: VQE, P.O. Box 3990, Columbus, OH 43218-3990 or e-mail vqe.chief@dla.mil. An online listing of products qualified to this specification may be found in the Qualified Products Database (QPD) at https://assist.daps.dla.mil.
  - 6.4 Supersession data. This specification supersedes DESC drawing 89009, dated 19 December 1989.
- 6.5 <u>JANC die versions</u>. The JANHC and JANKC die versions of these devices are covered under specification sheet MIL-PRF-19500/657.
- 6.6 <u>Changes from previous issue</u>. The margins of this specification are marked with asterisks to indicate where changes from the previous issue were made. This was done as a convenience only and the Government assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the last previous issue.

Custodians:

Army - CR Navy - EC Air Force - 85 NASA - NA DLA - CC Preparing activity: DLA - CC

(Project 5961-2012-009)

Review activities:

Army - SM Navy - AS, MC, OS Air Force - 19

<sup>\*</sup> NOTE: The activities listed above were interested in this document as of the date of this document. Since organizations and responsibilities can change, you should verify the currency of the information above using the ASSIST Online database at <a href="https://assist.daps.dla.mil/">https://assist.daps.dla.mil/</a>.